

**CLAIMS**

Having thus described our invention, what we claim as new and desire to secure by Letters Patent is as follows:

- 1       1. A lithography system, comprising:  
2               a reticle chamber having a reticle chamber opening;  
3               a reticle chamber maintenance panel which is removably mounted to  
4       the reticle chamber opening; and  
5               a reticle stage housed within the reticle chamber and accessible and  
6       removable through the reticle chamber opening.
- 1       2. The lithography system of claim 1, wherein the reticle stage is removable  
2       from the reticle chamber in a first direction which is in a plane substantially  
3       horizontal to a reticle table mounted to the reticle stage.
- 1       3. The lithography system of claim 2, wherein the reticle chamber  
2       maintenance panel is pivotably mounted to the reticle chamber.
- 1       4. The lithography system of claim 1, wherein the reticle chamber opening is  
2       at an angle substantially equal to or between 0° and 45° with relation to the  
3       reticle chamber.
- 1       5. The lithography system of claim 1, wherein the reticle chamber opening is  
2       at an angle at or greater than 45° with relation to the reticle chamber.
- 1       6. The lithography system of claim 1, further comprising:  
2               a projection optic system;

3 an illuminator optic system; and  
4 a reticle table mounted to the reticle stage and positionable between  
5 the projection optic system and the illuminator optic system.

1 7. The lithography system of claim 6, wherein the reticle table and the reticle  
2 stage are removable through the reticle chamber opening in a plane which is  
3 substantially perpendicular to a source illuminating from the illuminator optic  
4 system.

1 8. The lithography system of claim 7, further comprising a body structure  
2 which is mounted to a lower portion of the reticle chamber, the projection  
3 optic system and the illuminator optic system being mounted to the body  
4 structure.

1 9. The lithography system of claim 1, wherein the reticle chamber  
2 maintenance panel is semi-cylindrically shaped.

1 10. The lithography system of claim 1, wherein the reticle stage is removeable  
2 without disassembling the projection optic system or the illuminator optic  
3 system.

1 11. The lithography system of claim 1, wherein the reticle chamber opening  
2 provides substantially complete access to the reticle stage.

1 12. The lithography system of claim 1, wherein the reticle chamber opening  
2 provides access to substantially a center of gravity of the reticle stage.

1 13. A lithography system, comprising:

2 a reticle chamber having a reticle chamber angled opening,  
3 a reticle chamber maintenance panel which is removably mounted to  
4 the reticle chamber angled opening;  
5 an optical system for illuminating and projecting a source;  
6 a reticle stage having a reticle table, the reticle table positioned  
7 between components of the optical system and housed with the reticle stage  
8 within the reticle chamber,  
9 wherein the reticle chamber angled opening provides access to the  
10 reticle stage.

1 14. The lithography system of claim 13, wherein the reticle chamber angled  
2 opening provides access to the reticle stage at substantially a center of gravity.

1 15. The lithography system of claim 14, wherein the reticle stage is  
2 removable from the reticle chamber via the reticle chamber angled opening.

1 16. The lithography system of claim 14, wherein the reticle stage is  
2 removable from the reticle chamber via the reticle chamber angled opening in  
3 a first direction which is in a plane substantially horizontal to the reticle table.

1 17. The lithography system of claim 13, wherein the reticle chamber  
2 maintenance panel is pivotably mounted to the reticle chamber.

1 18. The lithography system of claim 13, wherein the reticle angled chamber  
2 opening is at an angle of approximately  $45^\circ$  with relation to the reticle  
3 chamber such that the reticle chamber maintenance panel is removed, the  
4 reticle stage partially extends from the reticle chamber.

- 1 19. The lithography system of claim 13, further comprising a body structure  
2 which is mounted to a lower portion of the reticle chamber, the projection  
3 optic and the illuminator optic being mounted to the body structure during the  
4 removal of the reticle table and the reticle stage.
- 1 20. The lithography system of claim 13, wherein the reticle chamber  
2 maintenance panel is semi-cylindrically shaped.